

Special Issue

Application of Artificial Intelligence (AI) in Chemical Science and Engineering

Message from the Guest Editor

This Special Issue will collect high-quality research and review papers on “Application of Artificial Intelligence (AI) in Chemical Science and Engineering”. Topics include, but not are limited to: the combination of deep learning with molecular dynamics and catalyst design; novel machine learning algorithms for chemical safety and chemical process control; the application of AI in the design and optimization of chemical unit equipment; AI in crystallization and other unit operations; AI in other fields of chemical science and engineering.

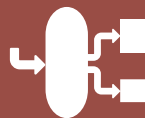
Guest Editor

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